



Atty. Dkt. No.	M#	Client Ref.
	306865	P-0393.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOWISCH et al.	
Appln. No.: 10/716,939	
Filing Date: November 20, 2003	
Examiner:	Group Art Unit: 2812

Date: March 26, 2004

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AM	AR 5,789,734	08/1998	TORIGOE et al.			
AM	BR 6,078,380	06/2000	TANIGUCHI et al.			
AM	CR 6,115,108	09/2000	CAPODIECI			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
AM	OR 1 251 402 A1	10/2002	EUROPE	BASELMANS et al.				
	PR							
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							
	WR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

AM	XR	Katsura OTAKI, "Asymmetric Properties of the Aerial Image in Extreme Ultraviolet Lithography," Jpn. J. Appl. Phys. 39:6819-6826 (2000)			
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

Examiner Alan Mathews

Date Considered: 5-3-2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



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Applicant: LOWISCH et al.	
Appln. No.: 10/716,939	
Filing Date: November 20, 2003	
Examiner: NOT ASSIGNED	Group Art Unit: 2812

Date: May 4, 2004 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR						
BR						
CR						
DR						
ER						
FR						
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HR						
IR						
JR						
KR						
LR						
MR						

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
AM	NR 1 271 247 A1	01/2003	EUROPE	Van der Werf et al.				
	OR							
	PR							
	QR							
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	TR							
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OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

AM	VR	Chen et al., "Simulation on a New Reflection Type Attenuated Phase Shifting Mask for Extreme Ultraviolet Lithography," SPIE, Vol. 3676, March 1999, pp. 578-586.				
	WR					
	XR					
	YR					
	ZR					
	AAR					

Examiner Alan Mathews Date Considered: 5-3-2005

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